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Name:	Examiner Hiteshew	Phone No.:	571.272.1463
Firm:	United States Patent and Trademark Office	Date:	October 30, 2002
Fax No.:	571.273.1473		
Subject:	U.S. Patent Application Serial No. 10/602,072		

FROM

Name	David M. Longo, Reg. No. 53,235	Phone No.:	202-408-4489
Fax # Verified by:	DML @ MD 749	# Pages (incl. this)	16
Our File No.:	04329.2470-01		

Confirmation Copy to Follow: No

Message:

Further to our conversation earlier today, we attach a copy of the Preliminary Amendment filed on June 24, 2003.

*Please verify that you now have all pages of the Preliminary Amendment.
Thank you.*

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PATENT
Customer No. 22,852
Attorney Docket No. 04329.2470-01

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
Shoji SETA, et al.) Group Art Unit: *Not Yet Assigned*
Cont. of Application No.: 09/739,905) Examiner: *Not Yet Assigned*
Filed: Herewith)
For: DRY ETCHING METHOD AND)
SEMICONDUCTOR DEVICE)
MANUFACTURING METHOD)

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

PRELIMINARY AMENDMENT

Prior to the examination of the above application, please amend this application as follows:

IN THE ABSTRACT:

Please replace the current Abstract with the Substitute Abstract attached on a separate page. The full text of the Abstract in clean form is as follows:

--A dry etching method comprises sequentially laminating a first insulating layer containing carbon and a second insulating layer containing carbon on a substrate, patterning the second insulating layer to form a mask; forming grooves in the first insulating layer by etching the first insulating layer with the second insulating layer used as a mask such that each of the grooves has a side surface and a bottom surface in the first insulating layer; and removing the

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